

IMPORTANT: Do not expose SU8 thk > 50um

VPG200 exposure parameters

Ref plate: 28mJ/cm²
Cr blank - Nanofilm SL (Soda Lime), Cr 90nm, PR AZ1512 530nm

Updated: GAR / Jan. 10th 2022

Illumination Factor L		[mJ/cm ²]	Beam Diam [μm]	CD [μm]
Fast	20mm	70,0	2,0	2,0
Standard	10mm	116,7	1,0	0,9
Advanced	4mm	147,4	0,6	0,7
Advanced ++	4mm 700px	#DIV/0!	0,6	0,5

	Dose [mJ/cm ²]	Available laser intensity	
		98%	
AZ ECI 0um76	100	Intensity = Dose / L	
	Intensity = Dose / L [%]	Int%	Nb. Exposure
20mm	143	71	2
10mm	86	86	1
4mm	68	68	1
4mm 700px	#DIV/0!	#DIV/0!	1

mode	Write Head	Speed [mm ² /min]	Pneumatic DeFocus (DF)	Intensity [%]	CDBias ZX [nm]	CDBias ZY [nm]	Expo area 110x110 mm ² Throughput (including handling) [5" mask/hour]
Fast	20mm	1960	0	40,0%	0	-100	8
Standard	10mm	980	20	24,0%	-50	-100	3,7
Advanced	4mm	190	-7	19,0%	-50	-150	0,9
Advanced ++ 700px; Unidirectional 1b	4mm 700px	130	-3		-50	-150	0,75

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' (speed 1.00)
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Attenuator setup Fail

Standard mask fab process (Order Cr-blank(s) at least 24 hours before booking)

Step 01 Convert your design using left hand linux workstation (free access, no booking, no login)
Step 02 Expose: VPG200 student/carrier wizard mode with above parameters
Step 03 Develop - etch Cr - strip resist Hamatech zone 06

One shot	or with intermediate check
4-5 inch Recipe 1	Recipe 6+3
6 inch reticules Recipe 11	Recipe 15+13
7 inch Recipe 11	Recipe 15+13

Critical Dimension (CD)

Direction dependant

vertical Only (array ls 1:1 duty ratio)